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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/599,035	09/18/2006	Yasuo Kitaoka	10873.1950USWO	3284
53148 HAMRE SCH	0/599,035 09/18/2006 Yasuo Kitaoka 53148 7590 01/07/2008 HAMRE, SCHUMANN, MUELLER & LARSON P.C.	EXAMINER		
P.O. BOX 2902		P.O. BOX 2902-0902 HITESHEW, FELISA CARLA		
MINNEAPOL	INNEAPOLIS, MN 55402		ART UNIT	PAPER NUMBER
			1792	
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			01/07/2008	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

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·	Application No.	Applicant(s)
	10/599,035	KITAOKA ET AL.
Office Action Summary	Examiner	Art Unit
·	Felisa C. Hiteshew	1792
The MAILING DATE of this communication ap Period for Reply	pears on the cover sheet w	vith the correspondence address
A SHORTENED STATUTORY PERIOD FOR REPL WHICHEVER IS LONGER, FROM THE MAILING Description of time may be available under the provisions of 37 CFR 1 after SIX (6) MONTHS from the mailing date of this communication. If NO period for reply is specified above, the maximum statutory period Failure to reply within the set or extended period for reply will, by statut Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMMUNI 136(a). In no event, however, may a will apply and will expire SIX (6) MOI te, cause the application to become A	ICATION. reply be timely filed NTHS from the mailing date of this communication. BANDONED (35 U.S.C. § 133).
Status		
1) ☐ Responsive to communication(s) filed on 2a) ☐ This action is FINAL . 2b) ☑ Thi 3) ☐ Since this application is in condition for allowated closed in accordance with the practice under	s action is non-final. ance except for formal mat	•
Disposition of Claims		
4)	awn from consideration. or election requirement.	
10) The drawing(s) filed on is/are: a) accomplicant may not request that any objection to the Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the E	e drawing(s) be held in abeyaretion is required if the drawing	nce. See 37 CFR 1.85(a). g(s) is objected to. See 37 CFR 1.121(d).
Priority under 35 U.S.C. § 119		
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority application from the International Burea * See the attached detailed Office action for a list	ts have been received. ts have been received in A prity documents have been uu (PCT Rule 17.2(a)).	Application No received in this National Stage
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO/SB/08) Paper No(s)/Mail Date 09/18/2006:	Paper No(s	Summary (PTO-413) s)/Mail Date nformal Patent Application

Priority

1. Receipt is acknowledged of papers submitted under 35 U.S.C. 119(a)-(d), which papers have been placed of record in the file.

Information Disclosure Statement

The PTOL 1449 of 09/18/2007 has been received, reviewed and considered.

Claim Rejections - 35 USC § 112

2. Claim 1 recites the limitation "...silicon carbide..." in line 2. There is insufficient antecedent basis for this limitation in the claim. Please insert the word -- a -- before the words "silicon carbide" for proper antecedence.

Claim 2 recites the limitation "...2H-SiC single crystal..." in 6. There is insufficient antecedent basis for this limitation in the claim. Please insert the word -- a-- before the phrase "...2H-SiC single crystal..." for proper antecedence. *Claim Rejections - 35 USC*

Claim Rejections - 35 USC § 102

3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 4. Claims 6-8 are rejected under 35 U.S.C. 102(b) as being anticipated by U. S. Patent No. 4, 349, 407 (Lundberg).

Lundberg teaches a method of growing a single crystal of beta SiC from the liquid phase using molten lithium, a. well known alkali metal and alkali earth metal. The speed at which the crystals can be grown is dependent on the temperature of the

solution, between the ranges of 1330*C to about 1500*C). In a preferred embodiment, beta SiC single crystals are formed by holding an excess of polycrystalline SiC in contact with the molten lithium at a temperature at which SiC dissolves therein and maintaining the resultant solution at this temperature for a time sufficient for beta SiC single crystals of the desired size to precipitate therefrom (See col. 1, lines 62-68 and col. 2, lines 1-65).

5. Claim18 and 19 are rejected under 35 U.S.C. 102(b) as being anticipated by U.S. Patent No. 5,718,760A (Carter, et al).

Carter, et al '760A teaches SiC single crystals of different polytypes (e.g. 2H, 6H,4H, 8H, 15R and 3C) (See col. 2, lines 14-19; lines 41-55; and col. 4, lines 3-8). *Claim*

Rejections - 35 USC § 103

- 6. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 7. This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to

consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

8.

9. Claims 1-5, 9-13 and 17 rejected under 35 U.S.C. 103(a) as being unpatentable over U.S. Patent No. 4, 349,407 (Lundberg) in view of U.S. Patent No. 3,053,635 (Shockley).

Lundberg teaches a method of growing a single crystal of beta SiC from the liquid phase using molten lithium, a. well known alkali metal and alkali earth metal. The speed at which the crystals can be grown is dependent on the temperature of the solution, between the ranges of 1330*C to about 1500*C). In a preferred embodiment, beta SiC single crystals are formed by holding an excess of polycrystalline SiC in contact with the molten lithium at a temperature at which SiC dissolves therein and maintaining the resultant solution at this temperature for a time sufficient for beta SiC single crystals of the desired size to precipitate therefrom (See col. 1, lines 62-68 and col. 2, lines 1-65).

The difference being that Lundberg does not exactly teach a method for producing a SiC single crystal, wherein silicon and carbon are dissolved in an alkali metal flux at different temperatures, a 2H-SiC or 3C-SiC single crystal, cooling the alkali metal flux, a carbon (graphite) based reaction vessel using a pressurized atmosphere.

Shockley teaches a molten metal or alloy in solution using carbon and silicon to form a liquid metal or alloy solvent. The concentration of carbon and silicon at a predetermined temperature for the concentration of silicon carbide is at saturation. A

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small localized region of the solution is then cooled and supersaturated with silicon carbide which is precipitated in crystalline form from the solution. The temperature in the small region may be lowered by inserting a SiC seed crystal into the solution. The localized region adjacent the seed is supersaturated and SiC deposits on the seed in its crystalline form. The seed and crystal forming thereon may be continuously withdrawn from the solution as silicon and carbon to continuously be added to maintain the proper concentration of SiC in the solution. Preferably, a large temperature difference should exist between saturation and spontaneous nucleation of SiC in order to permit growth of a single crystal from a cooled zone within a graphite crucible (See col. 1, lines 43-72 and col. 2, lines 1-19). However, in the absence of unobvious results, it would have been obvious to one of ordinary skill in the art to determine through routine experimentation modifying and optimizing the process parameter teachings, as taught by Lungberg, with the similar and optimal process parameter teachings, as taught by Shockley in order to ensure proper orientation. The motivation being able to produce economically relatively large and homogeneous SiC single crystals of high purity.

U. S. Patent No. 3,669,763 (Perusek) is being cited for it's teaching of using argon as an inert gas during the production of SiC single crystals (See col. 2, lines 38-50.)

It is sufficient that the reference(s) clearly suggest doing what the applicant(s) have done. In re Gershon 152 USPQ 602.

2 step test for analogous art: 1) Decide if art is in the field of the inventors endeaver.

2) if not, determine if reference is reasonably pertinent to the particular problem with which the inventor was involved. *In re Deminski* 230 USPQ 313, 315 (Fed. Cir. 1986); *Stratoflex Inc. v. Aeroquip Corp.* 218 USPQ 871, 876 (CCPA 1983); *In re Wood* 202 USPQ 171, 174 (CCPA 1979).

A reference is good not only for what it teaches by direct anticipation but also for what one of ordinary skill might reasonably infer from the teachings. In re Opprect 12 USPQ 2d 1235, 1236 (CAFC 1989); In re Bode 193 USPQ 12; In re Lamberti 192 USPQ 278; In re Bozek 163 USPQ 545, 549 (CCPA 1969); In re Van Mater 144 USPQ 421; In re Jacoby 135 USPQ 317; In re LeGrice 133 USPQ 365; In re Preda 159 USPQ 342 (CCPA 1968).

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Felisa Hiteshew whose telephone number is (571) 272-1463. The examiner can normally be reached on Mondays through Thursday from 5:30 AM to 4:00 PM with Fridays off.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Michael Barr, can be reached on (571) 272-1414. The fax phone number for the organization where this application or proceeding is assigned is (571) 273-1463.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through

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http://pair-direct.uspto.gov. Should you have questions on access to the Private

PAIR system, contact the Electronic Business Center (EBC) at 866- 217-9197

(toll-free).

FELISA HITESHEW PRIMARY EXAMINER

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